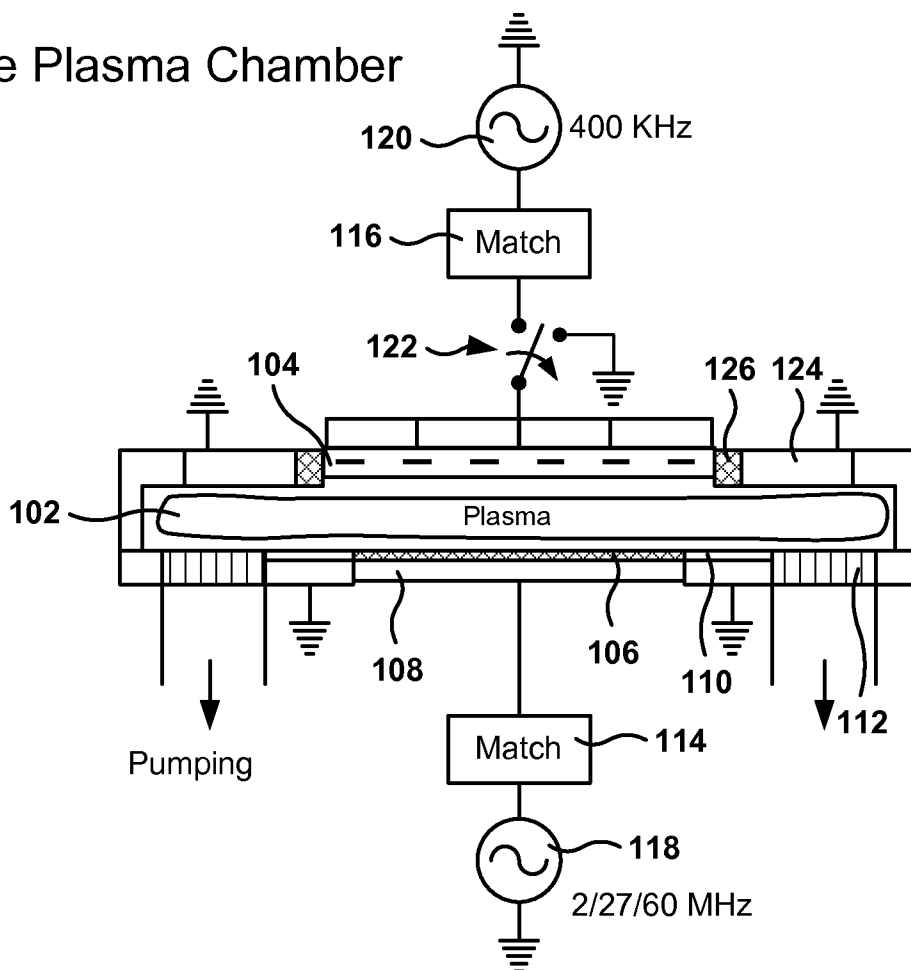
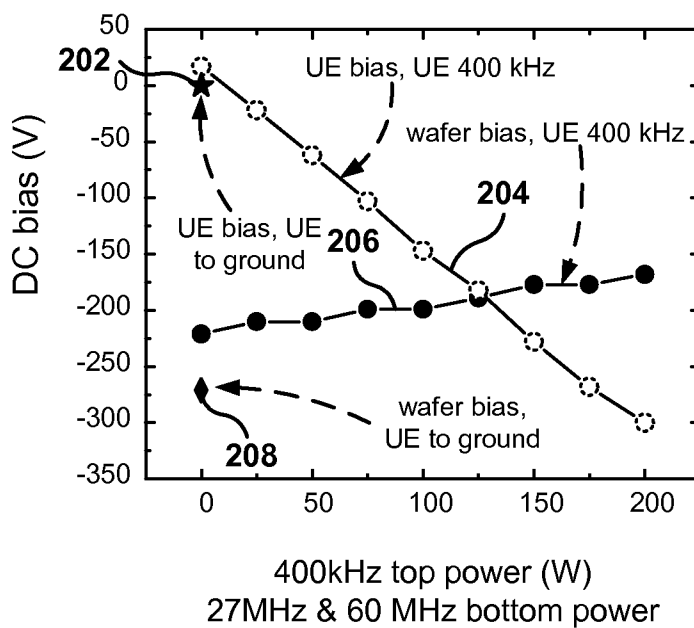


# Triode Plasma Chamber



**Fig. 1**



**Fig. 2**

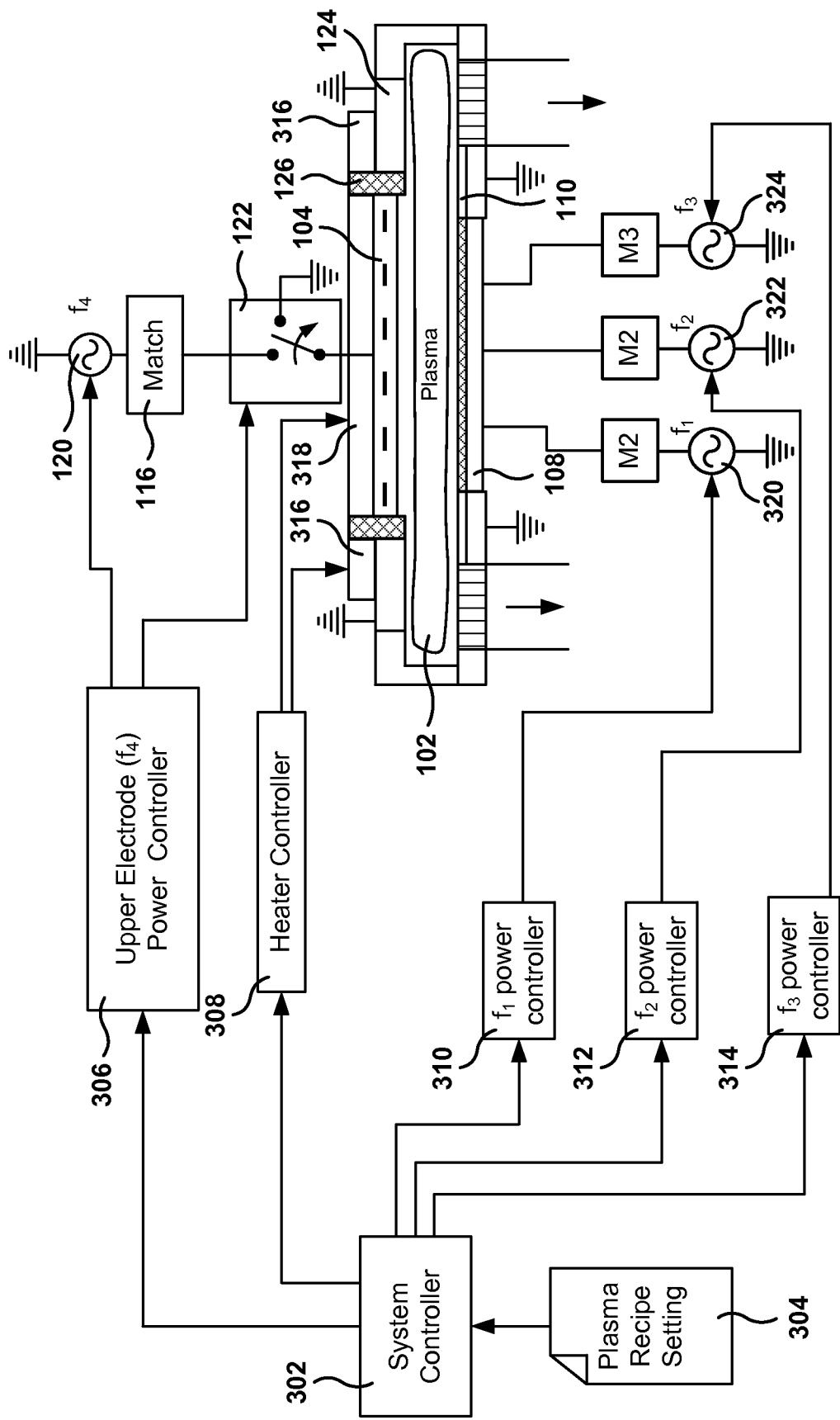


Fig. 3

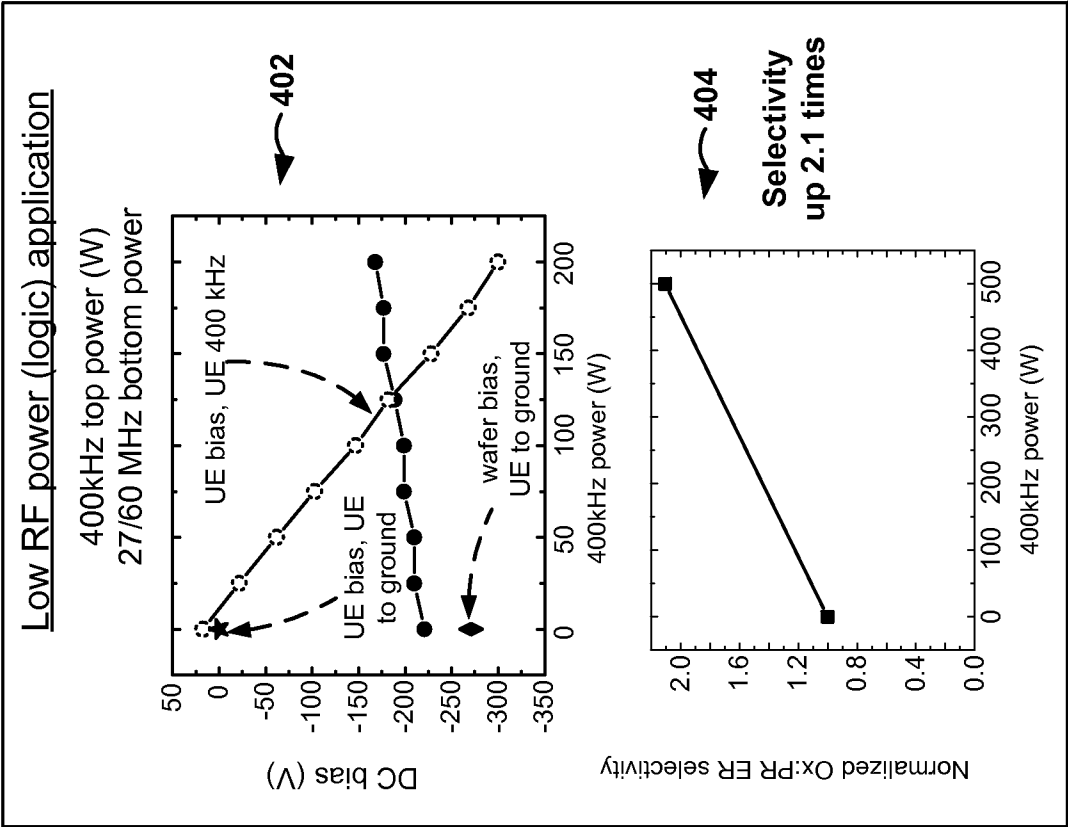


Fig. 4A

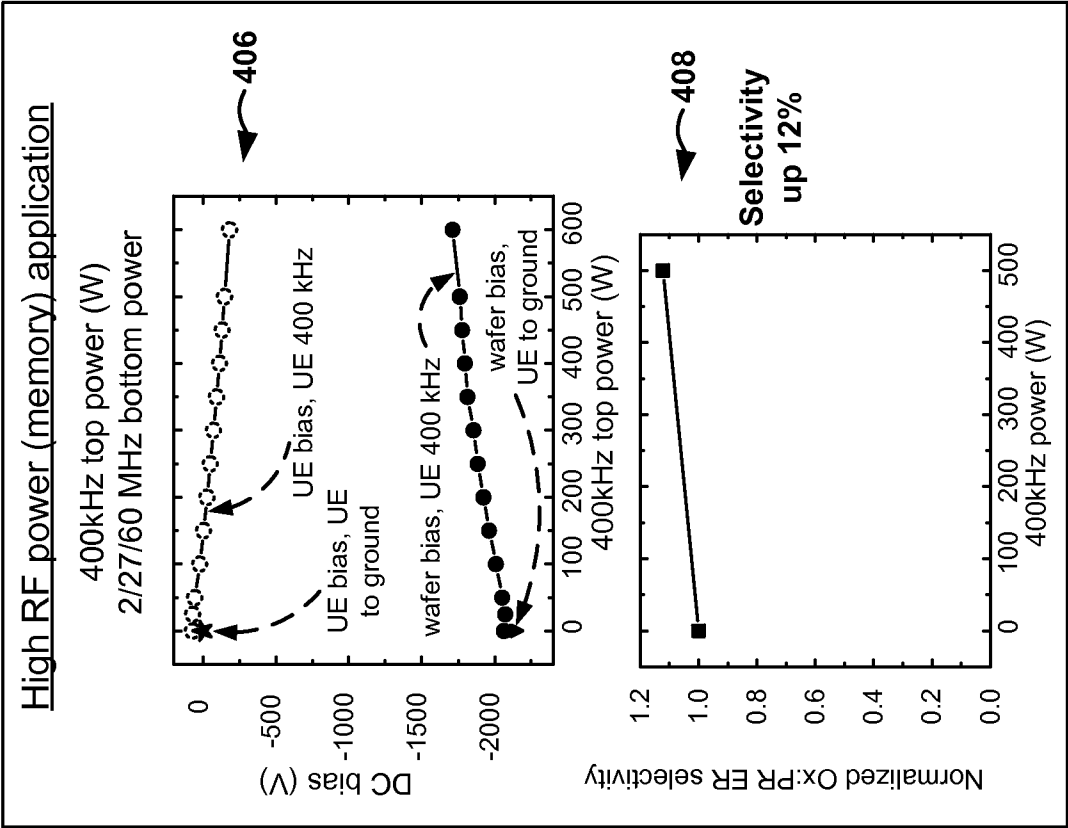


Fig. 4B

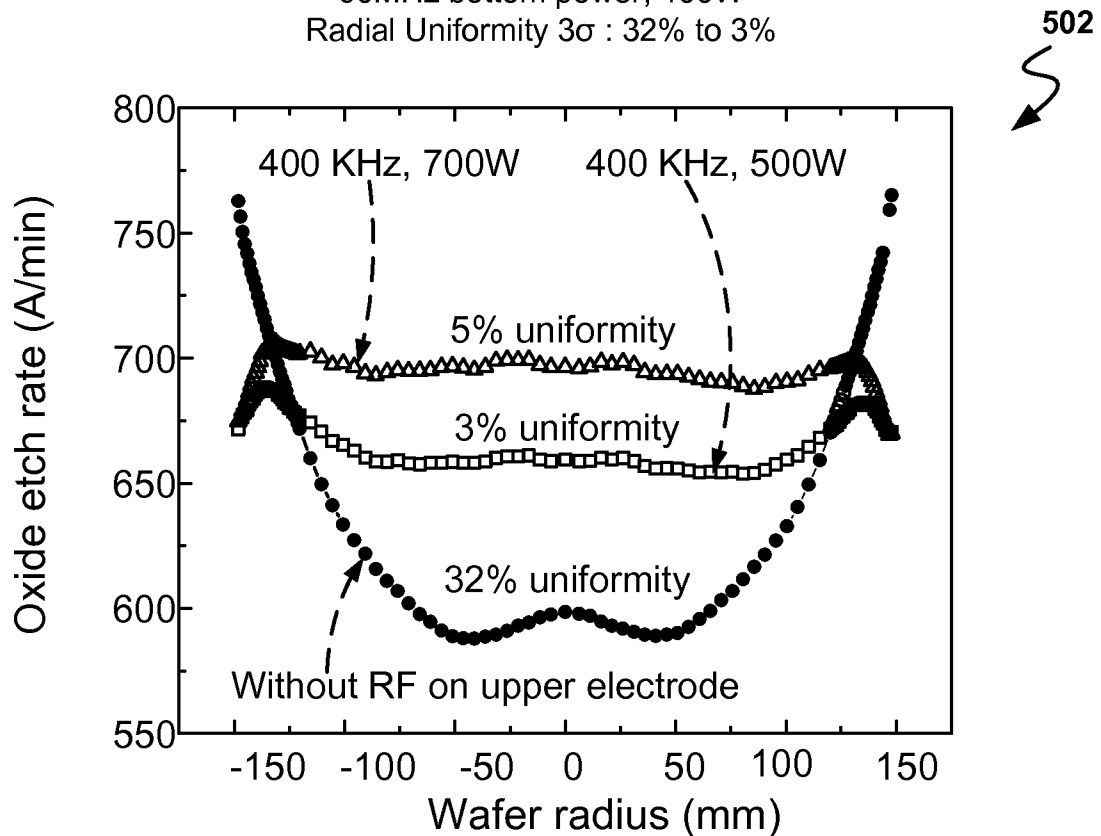
## Oxide etch rate radial uniformity control with top power

Power on upper electrode improves radial etch rate uniformity

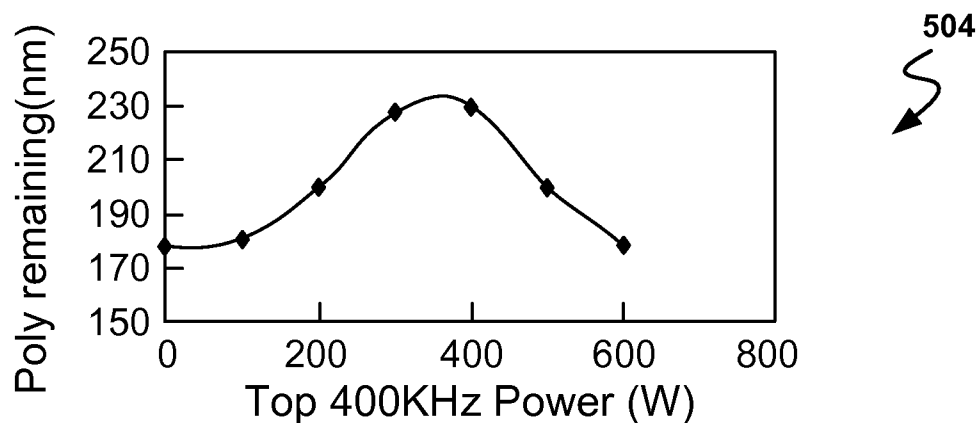
400kHz top power 0W, 500W, 700W

60MHz bottom power, 400W

Radial Uniformity  $3\sigma$  : 32% to 3%



**Fig. 5A**



**Fig. 5B**

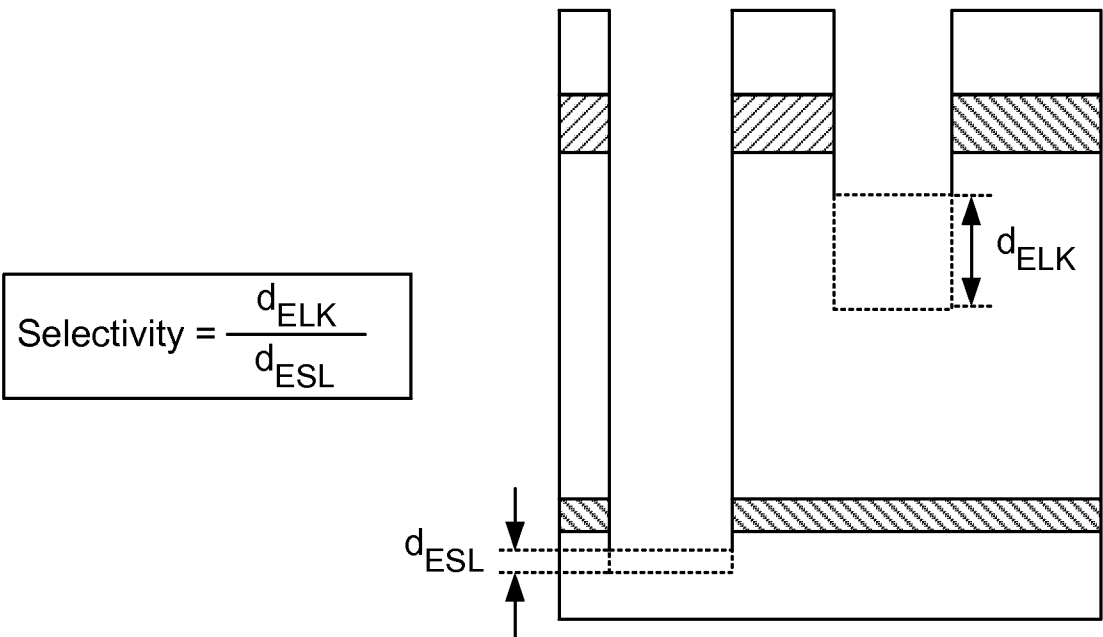


Fig. 6

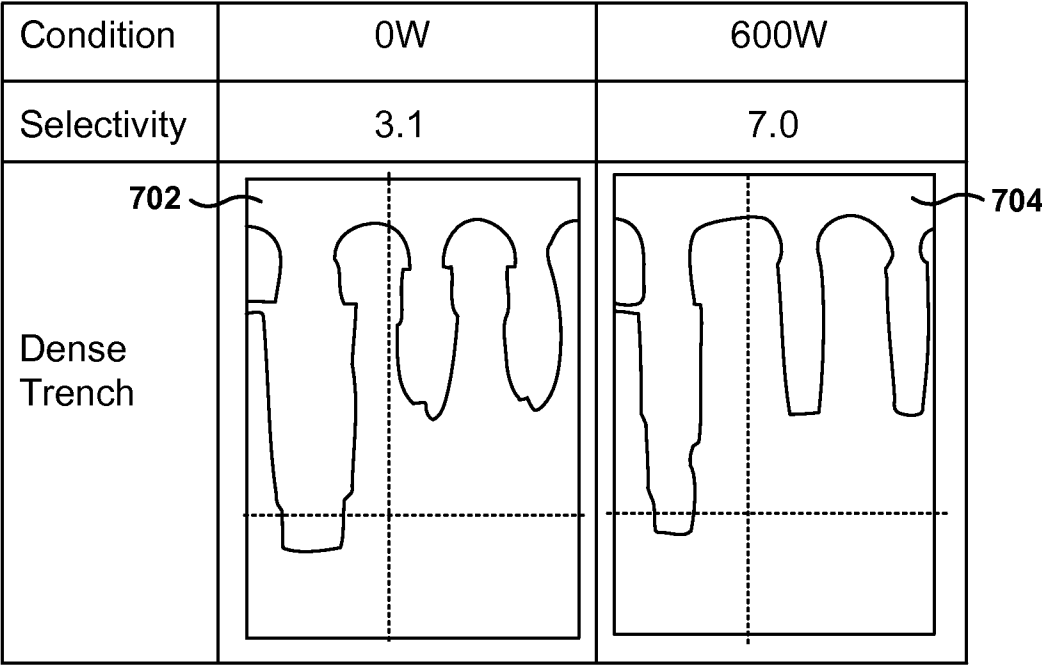
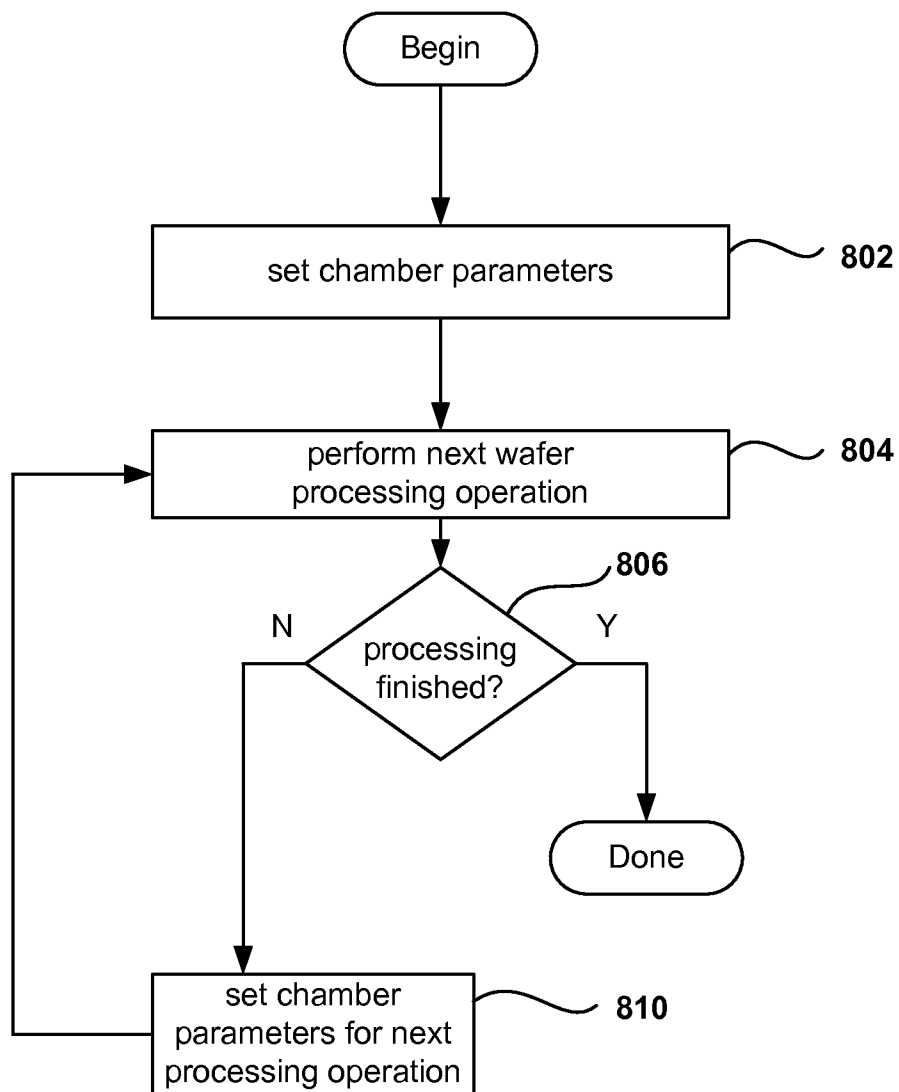


Fig. 7

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**Fig. 8**

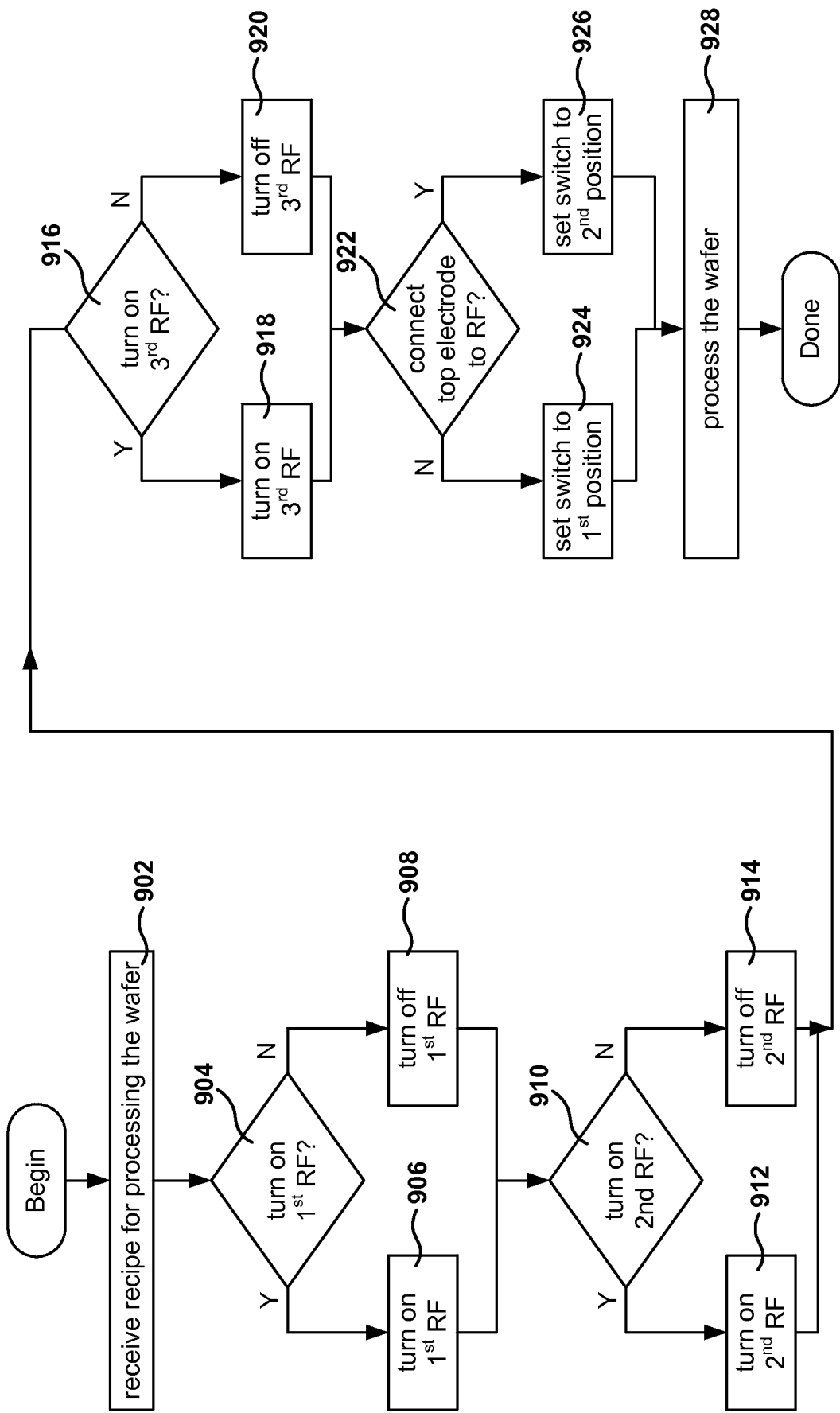
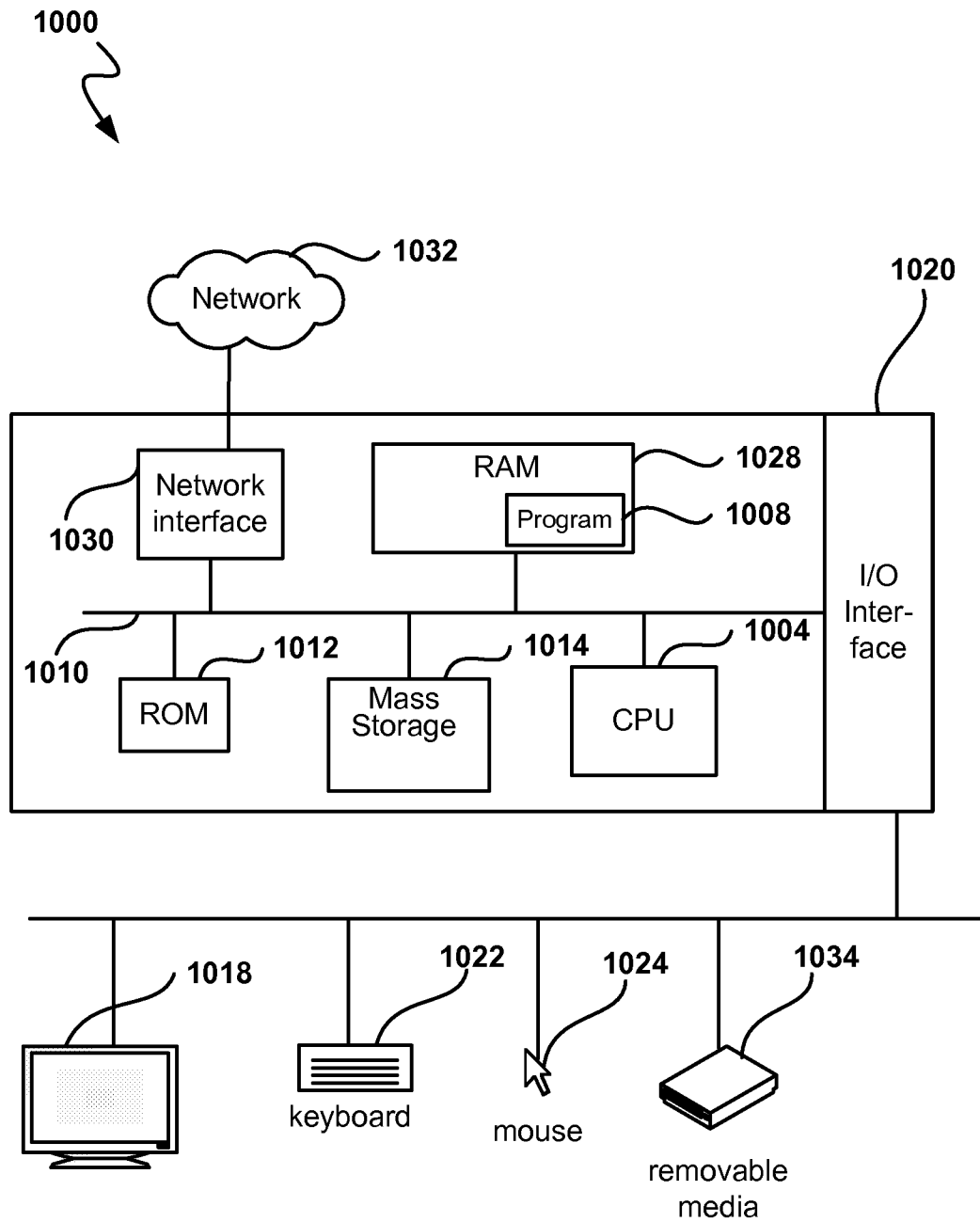


Fig. 9

**Fig. 10**